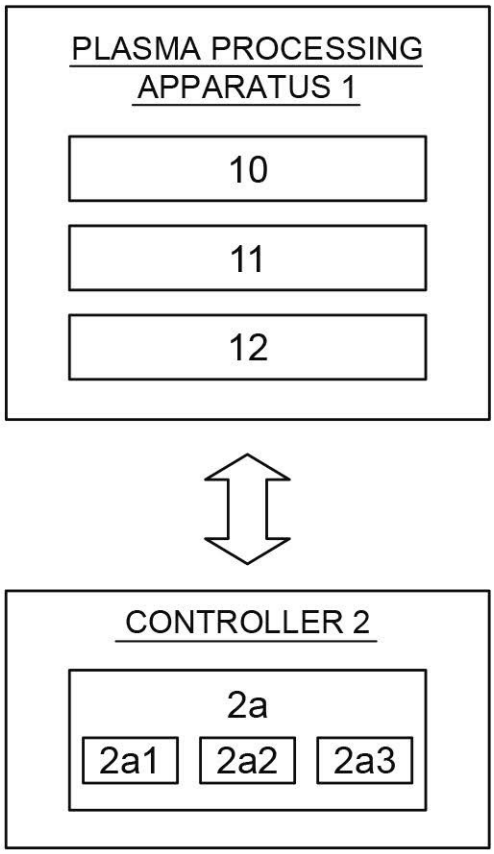
Fig.1


PLASMA PROCESSING APPARATUS 1
10
11
12
CONTROLLER 2
2a
2a1
2a2
2a3

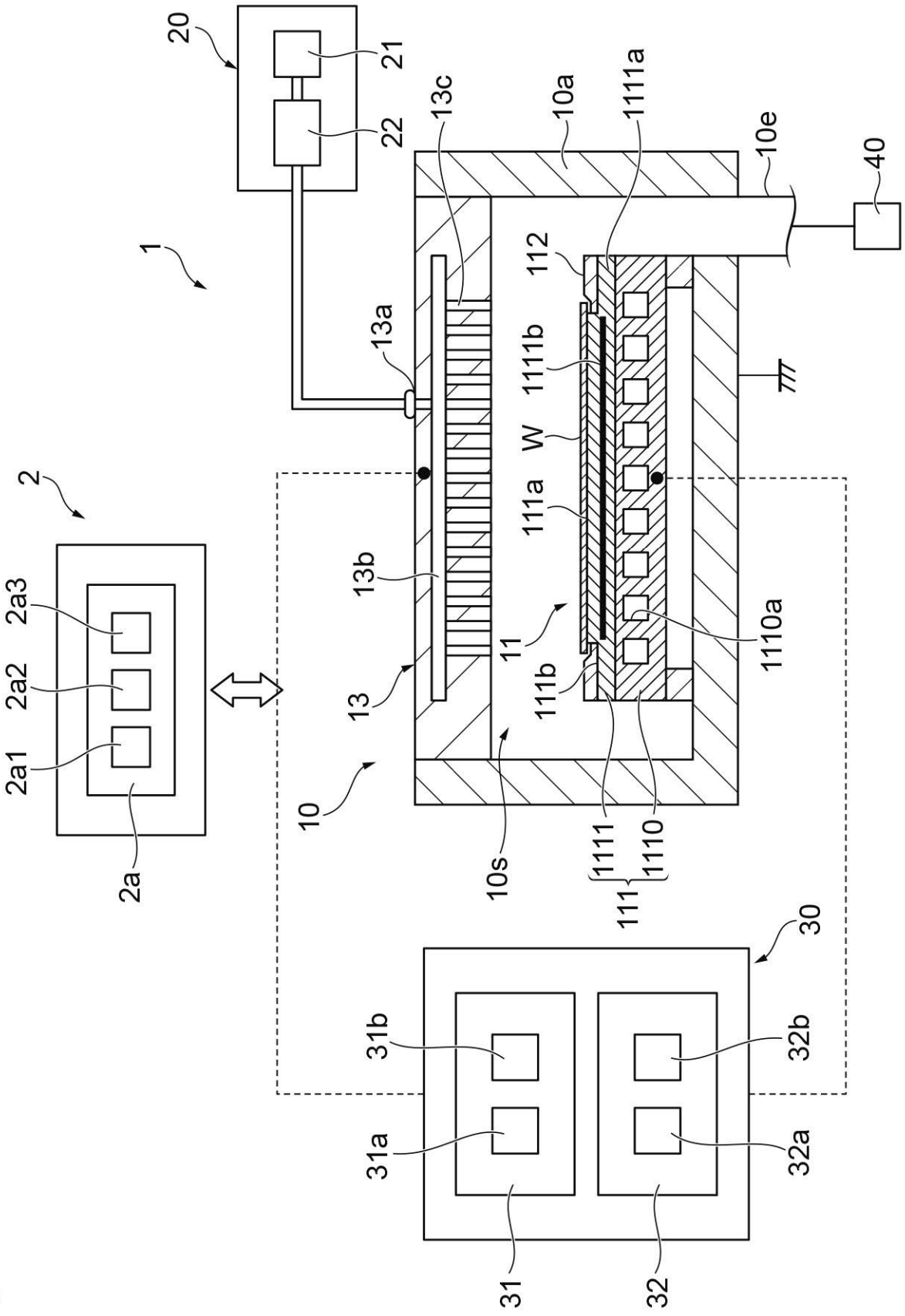

20
21
22
13c
10a
1111a
10e
40
1
112
13a
1111b
W
111a
2
2a3
2a2
2a1
13b
11
1110a
13
111b
10
10s
1111
1110
111
2a
30
31b
32b
31a
32a
31
32

Fig.2

Fig.3

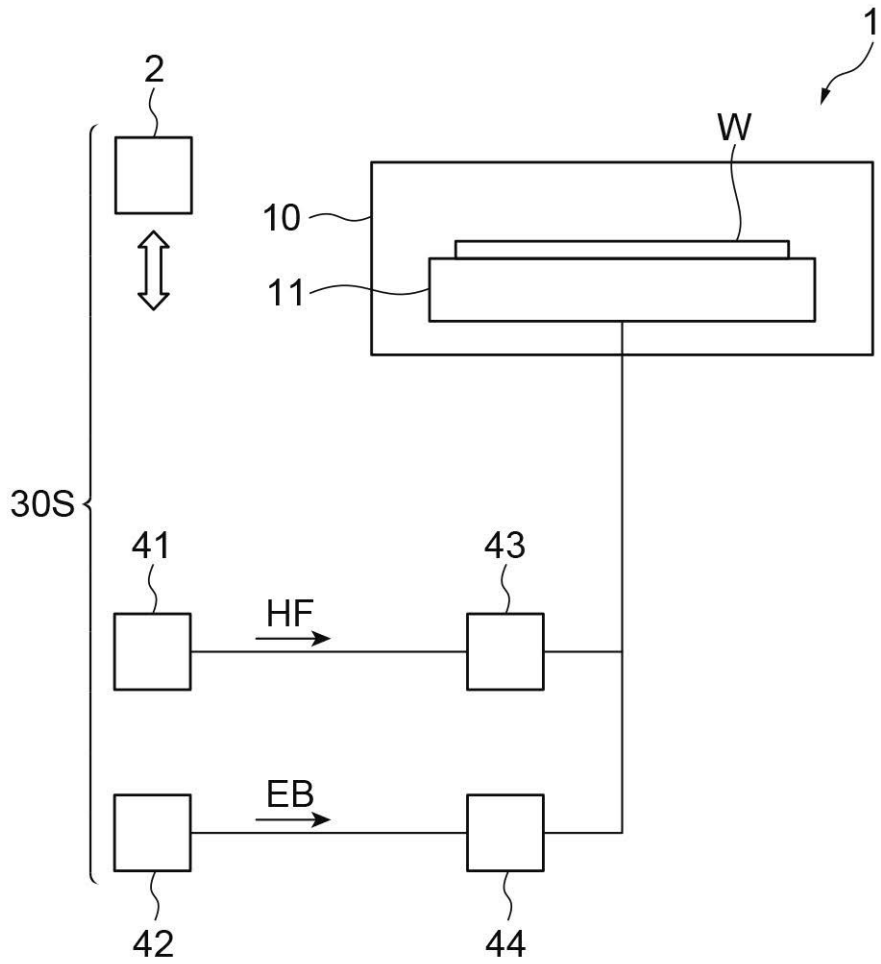


Fig.4

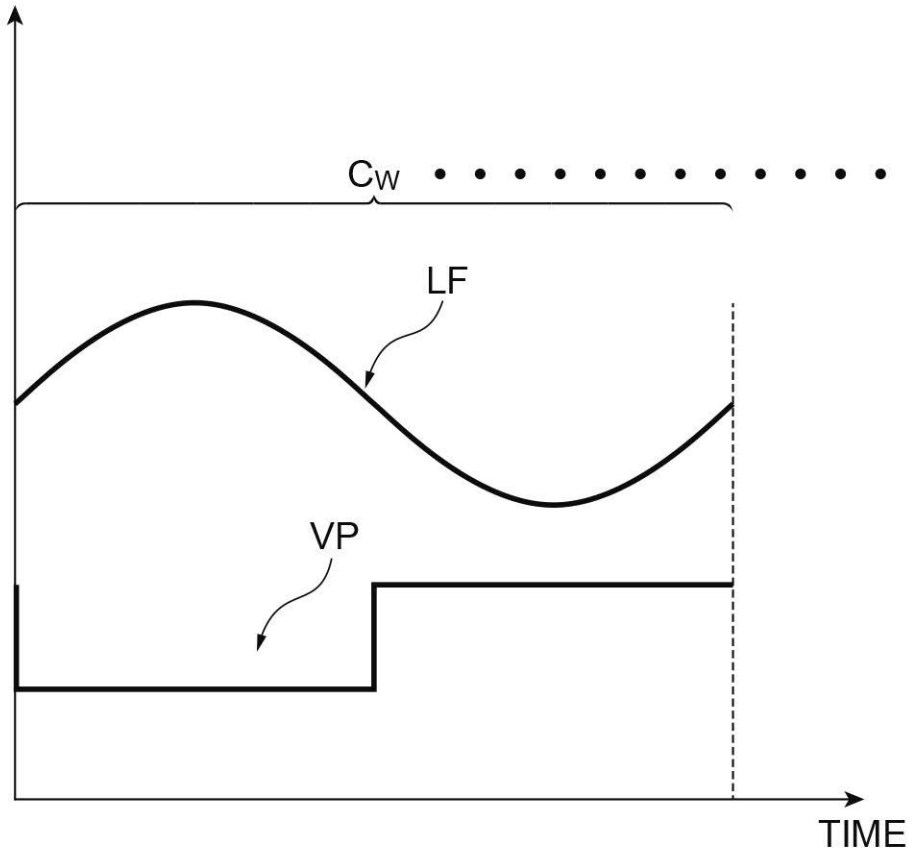


Fig.5

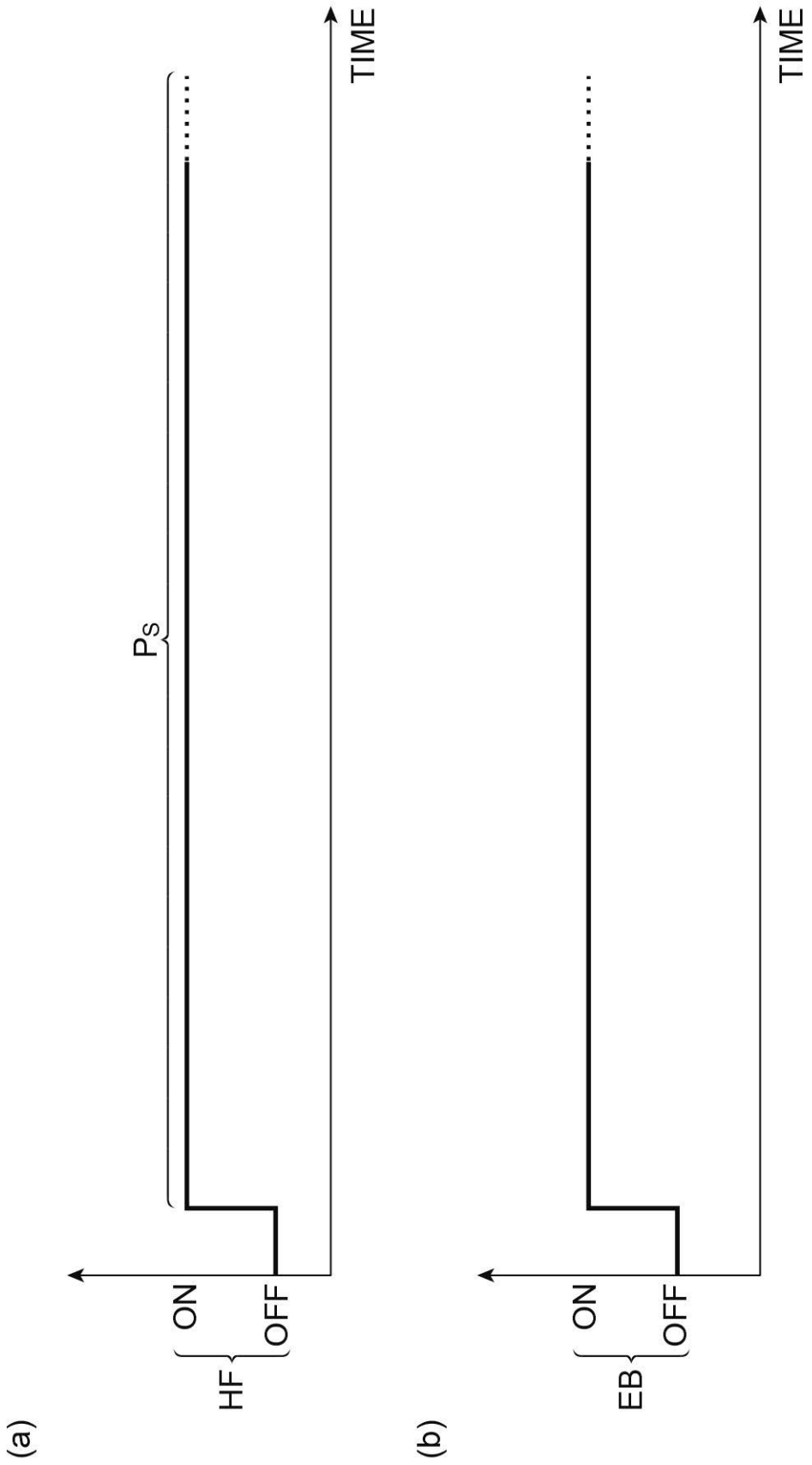


Fig.6

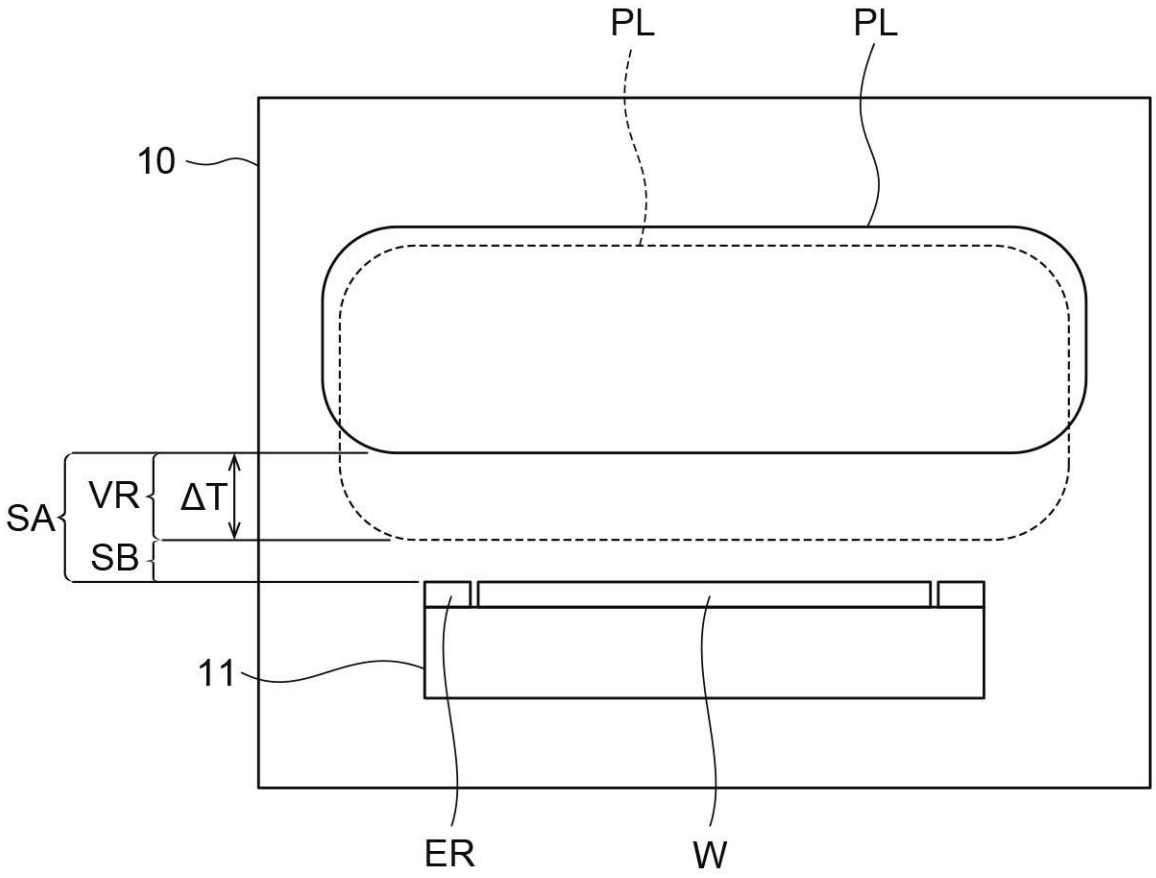


Fig.7

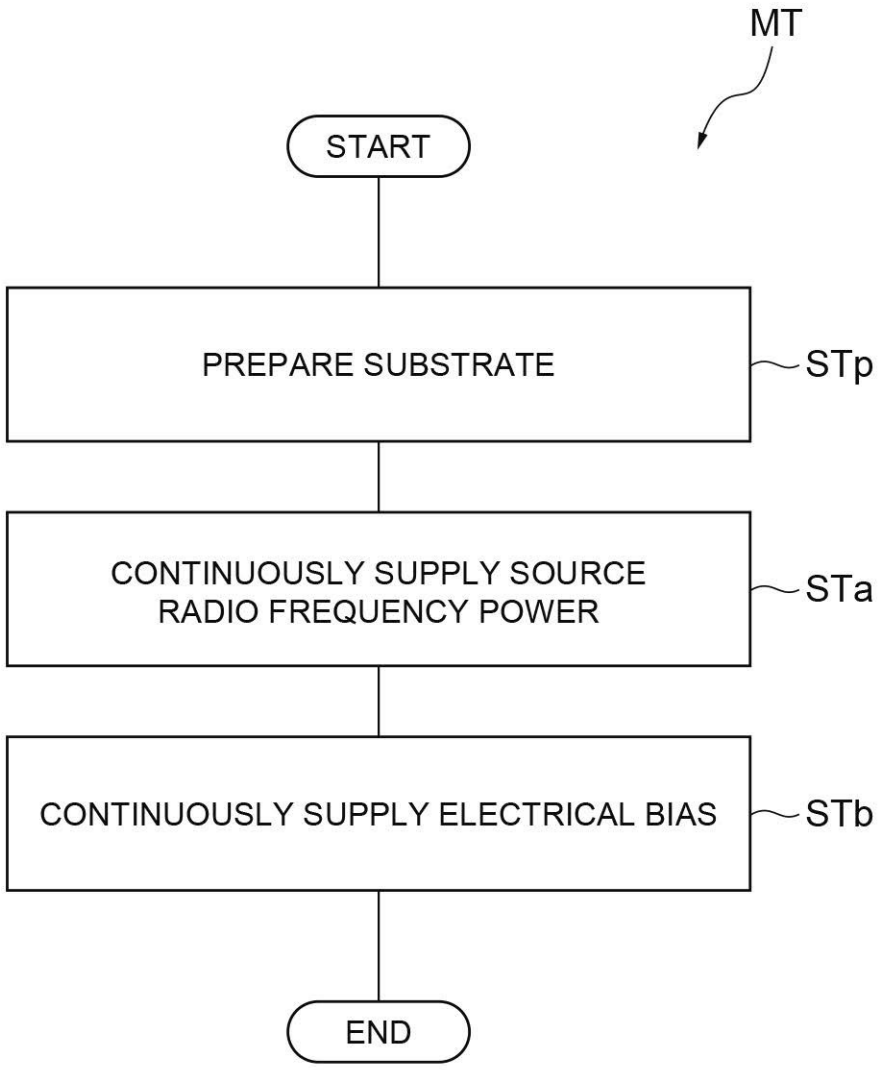

MT
START
PREPARE SUBSTRATE
STp
CONTINUOUSLY SUPPLY SOURCE RADIO FREQUENCY POWER
STa
CONTINUOUSLY SUPPLY ELECTRICAL BIAS
STb
END

Fig.8

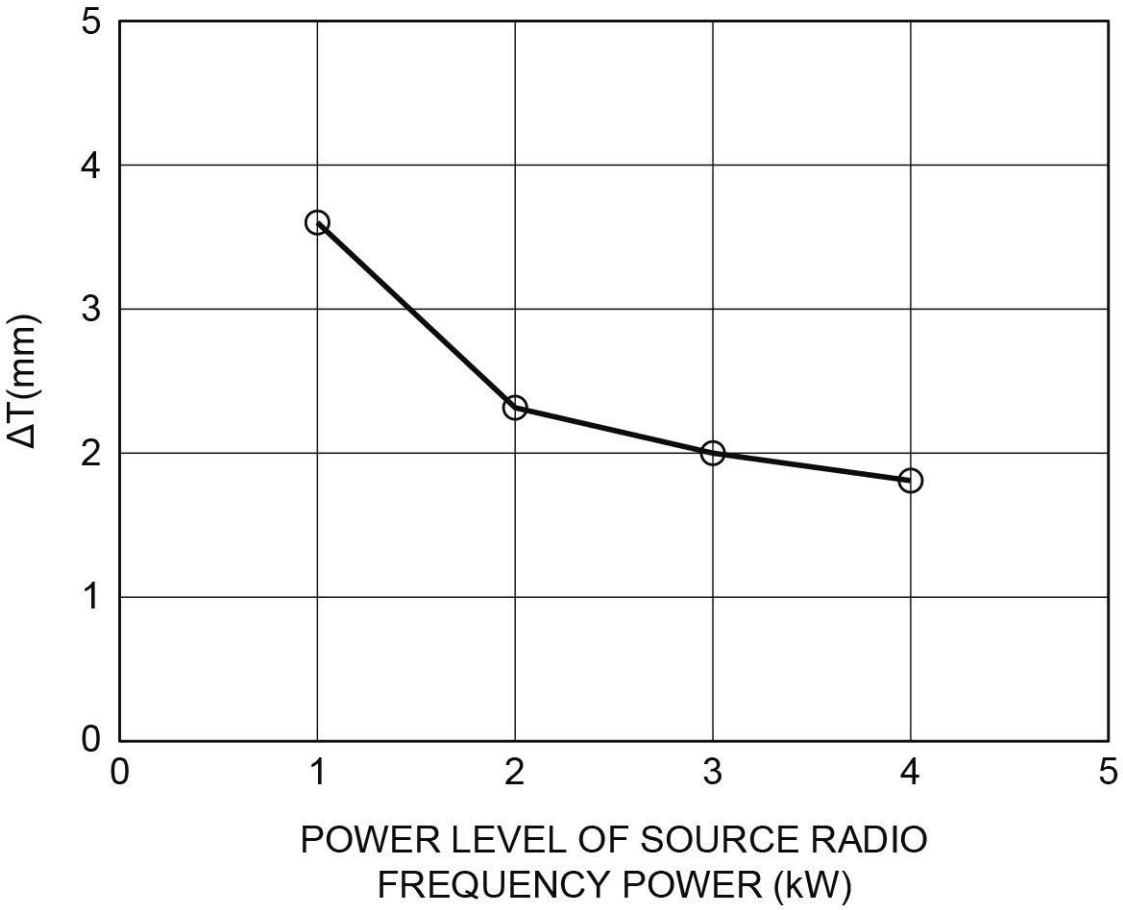

5
4
3
2
1
0
ΔT(mm)
0
1
2
3
4
5
POWER LEVEL OF SOURCE RADIO FREQUENCY POWER (kW)

Fig.9

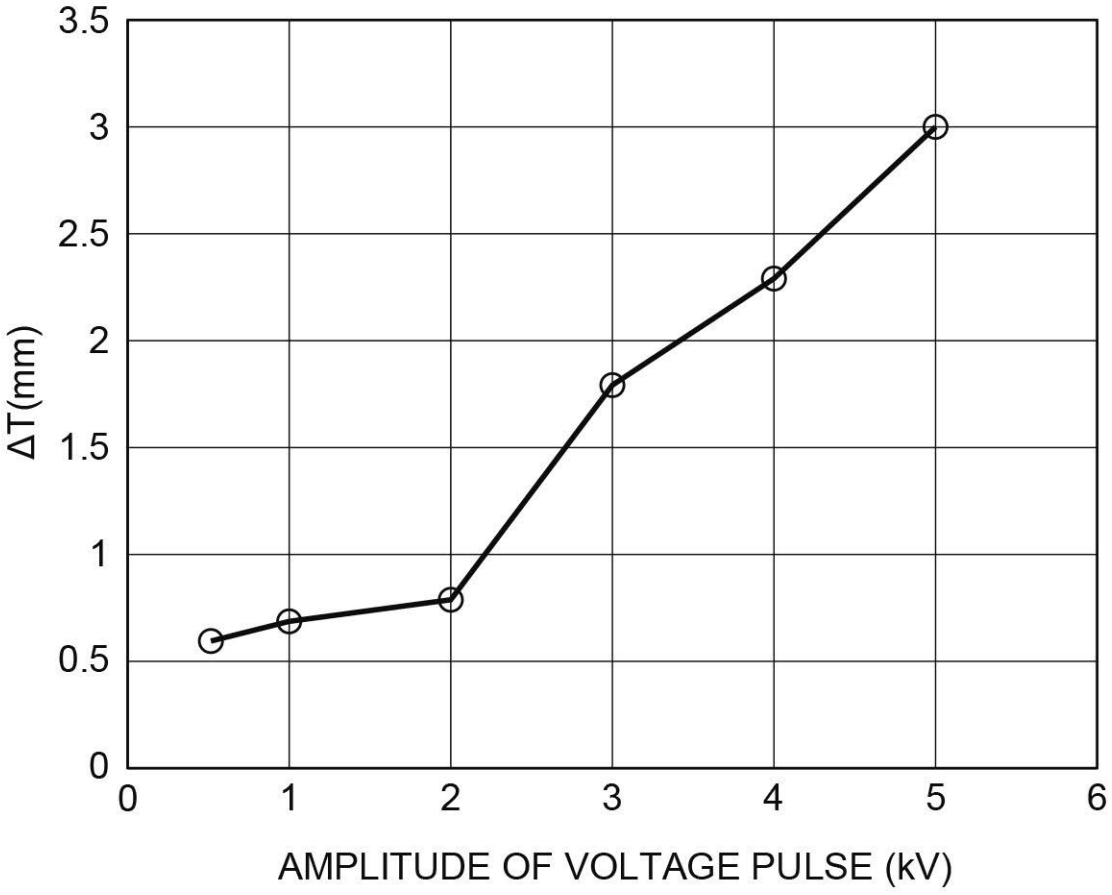


Fig.10

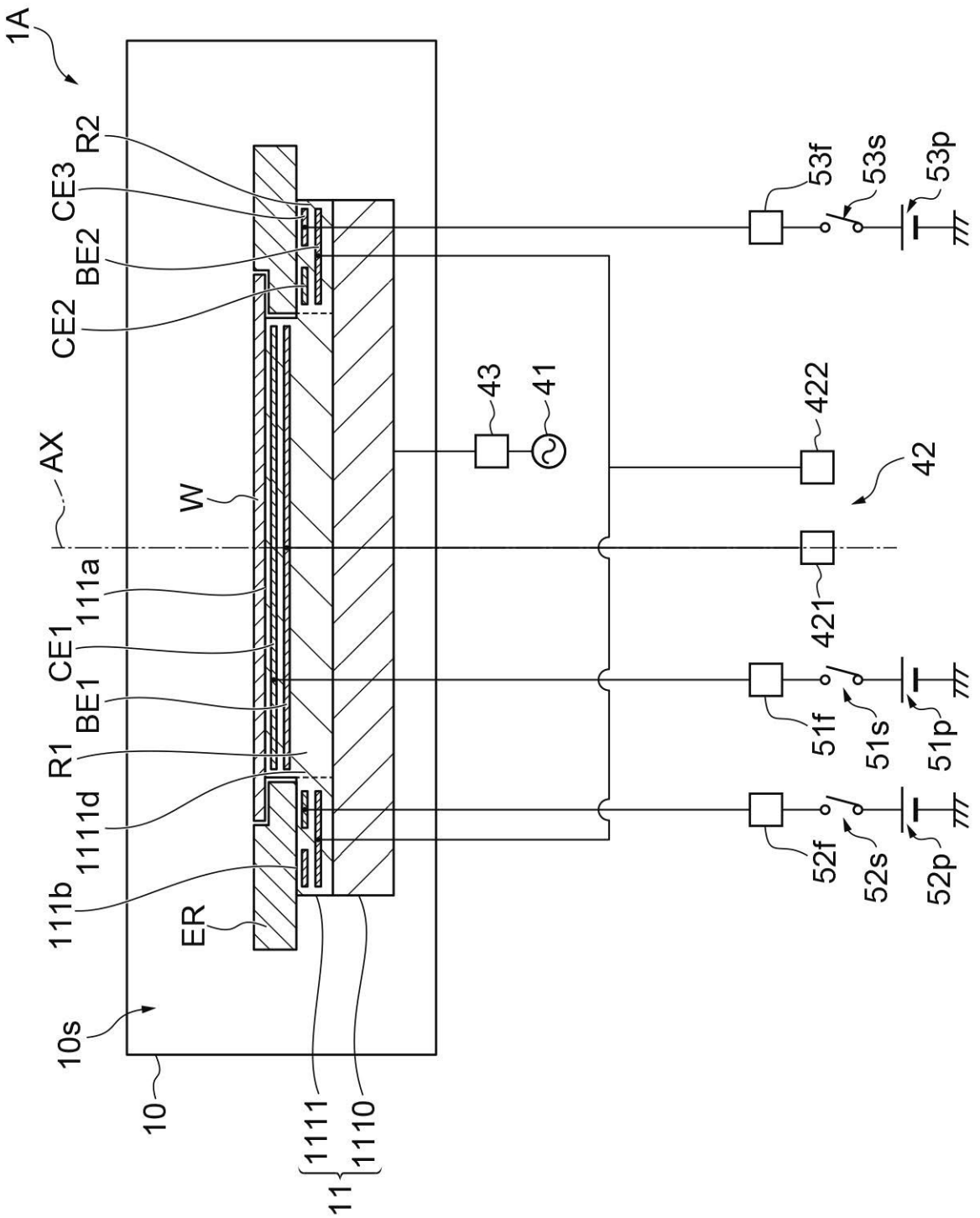
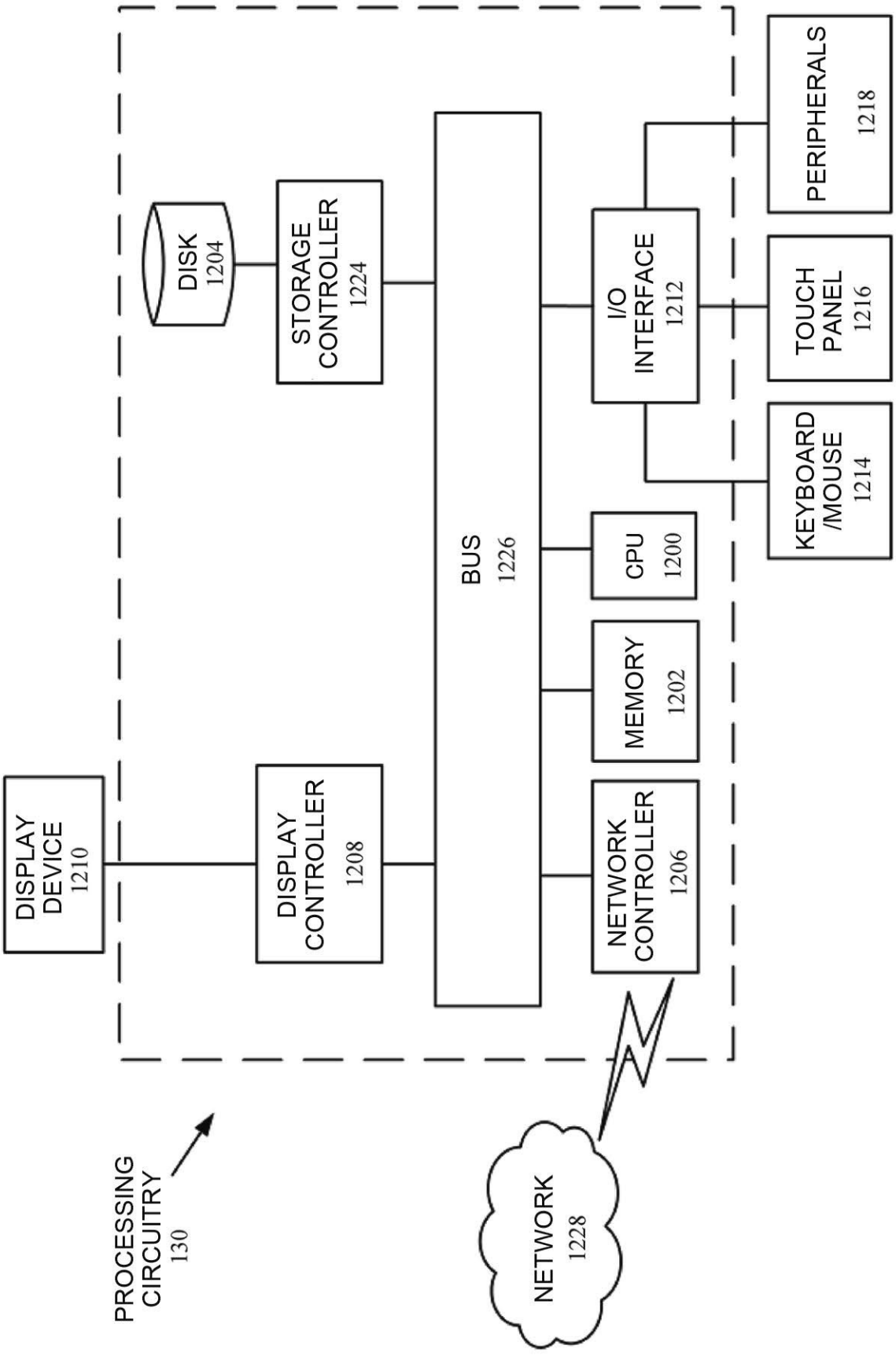

1A
R2
CE3
BE2
CE2
AX
W
111a
CE1
BE1
R1
1111d
111b
ER
10s
10
1111
1110
11
43
41
422
42
421
53f
53s
53p
51f
51s
51p
52f
52s
52p

Fig.11


PROCESSING CIRCUITRY 130
NETWORK 1228
DISPLAY DEVICE 1210
DISPLAY CONTROLLER 1208
DISK 1204
STORAGE CONTROLLER 1224
BUS 1226
NETWORK CONTROLLER 1206
MEMORY 1202
CPU 1200
I/O INTERFACE 1212
KEYBOARD /MOUSE 1214
TOUCH PANEL 1216
PERIPHERALS 1218